

Session Title:	[TB2] Advanced CMP Process
Session Date:	November 15 (Tue.), 2022
Session Time:	11:20-12:25
Session Room:	Room B (Grand Ballroom 1, 2F)
Session Chair:	Prof. Jingoo Park (Hanyang Univ., Korea)

[TB2-1] [Plenary]

11:20-12:05

12:05-12:25

Scaling Down and Stacking Up: How the Trends in Semiconductors are affecting Chemical-Mechanical Planarization (CMP)

Wei-Tsu Tseng (IBM Research, USA)

[TB2-2]

Advances in CMP Conditioning Disk Technology

Yongsik Moon, Kyoung-Kuk Kwack, Joohan Lee, Jongjae Lee, Youngtae Jeon, and Juhee Lee (Ehwa Diamond Co., Ltd., Korea)